L Number	Hits	Search Text	DB	Time stamp
73	181	(117/98 or 117/107).ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/18 16:12
74	8	((117/98 or 117/107).ccls.) and (atomic near2 layer near2 (deposit$5 or epitax$6) or ale or ald)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/18 16:15
75	35	((117/98 or 117/107).ccls.) and rotat$5 near10 (gas$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/18 16:16
76	50	(thomas near2 omstead or karl near2 levy).in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/18 16:17
77	3	((thomas near2 omstead or karl near2 levy).in.) and (ald or ale or atomic near2 layer near2 (deposit$7 or epitax$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/18 16:17
-	11832	(ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:28
-	2166	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) and (module or station)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:11
-	0	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) and (module or station) near5 plural%6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:11
-	290	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) and (module or station) near5 plural$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:11
-	9	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) same (module or station) near5 plural$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:17
-	0	sequential near2 deposit$5 near2 module	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:18
-	1	sequent$5 near2 deposit$5 near2 module	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:18
-	7	sequent$5 near4 deposit$5 near5 module	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:18
-	435	novellus.as.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:20

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–	5	novellus.as. and ald	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:19
–	24	novellus.as. and module near5 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 13:21
–	80	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) and module near5 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 15:16
–	2	5879459.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 14:51
–	1374	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) and (wafer or substrate) near10 (transfer$5 or transport$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 15:16
–	216	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) same (wafer or substrate) near10 (transfer$5 or transport$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/29 15:17
–	190	((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))) same (wafer or substrate) near5 (transfer$5 or transport$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:27
–	13	("4533410" | "4951601" | "5013683" | "5281274" | "5298452" | "5310698" | "5527733" | "5793109" | "5916365" | "6048781" | "6056849" | "6207005" | "6319553" | "2002/0108714").PN.	USPAT	2004/07/30 10:02
–	3672	rotat$5 near5 ball near5 valve	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:28
–	2132	rota$5 near2 ball near2 valve	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:28
–	11832	(ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:28
–	2	(rota$5 near2 ball near2 valve) and ((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:29
–	0	(rota$5 near2 ball near2 valve) and (CVD or chemical near2 vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:30
–	0	((rota$5 near2 ball near2 valve) and (CVD or chemical near2 vapor near2 deposit$5)) and 117/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 11:30

-	44	(rota$5 near2 ball near2 valve) near10 gas$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 12:05
-	70035	gas$4 near US-20020170671-A1.DID. curtain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 12:06
-	139	(gas$4 near US-20020170671-A1.DID. curtain) and ((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 12:06
-	16	gas$4 near US-20020170671-A1.DID. curtain same transfer and ((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 12:07
-	47	gas$4 near5 curtain and ((ald or ale or atomic near2 layer near2 (deposit$5 or epitax$5) or sequential near2 (cvd or deposit$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 12:07
-	108	manifold near10 showerhead and (CVD or vapor near2 deposit$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:18
-	32	manifold near10 showerhead same (CVD or vapor near2 deposit$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:37
-	3835	gas$4 near5 curtain	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:38
-	268	gas$4 near5 curtain and vapor near2 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:39
-	58	gas$4 near5 curtain same vapor near2 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:43
-	22	gas$4 near5 curtain and (vapor near2 deposit$4) and (plural$5 or multipl$5) near5 (zone or station$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 14:46
-	2	6143082.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:48
-	489	plasma near10 (atomic near2 layer near2 (deposit$5 or epitax$4) or ale or ald)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:49
-	19	plasma near10 (atomic near2 layer near2 (deposit$5 or epitax$4) or ale or ald) and 117/$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:51

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-	280	plasma near10 (atomic near2 layer near2 (deposit$5 or epitax$4) or ale or ald) near3 (enhanc$5 or assist$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:51
-	195	plasma near5 (atomic near2 layer near2 (deposit$5 or epitax$4) or ale or ald) near3 (enhanc$5 or assist$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:52
-	110	plasma near2 (atomic near2 layer near2 (deposit$5 or epitax$4) or ale or ald) near3 (enhanc$5 or assist$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 15:55
-	2	5916365.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:36
-	389	plasma near5 (CVD or chemical near2 vapor near2 deposit$5 or ale or ald or atomic near2 layer near2 (deposit$5 or epitax$4)).ti. and bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:40
-	33	plasma near5 (CVD or chemical near2 vapor near2 deposit$5 or ale or ald or atomic near2 layer near2 (deposit$5 or epitax$4)).ti. and bias$5 near5 (susceptor or holder)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:55
-	6	(plasma near5 (CVD or chemical near2 vapor near2 deposit$5 or ale or ald or atomic near2 layer near2 (deposit$5 or epitax$4)).ti. and bias$5 near5 (susceptor or holder)) and showerhead	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:38
-	23	plasma near5 (CVD or chemical near2 vapor near2 deposit$5 or ale or ald or atomic near2 layer near2 (deposit$5 or epitax$4)).ti. and bias$5 same showerhead	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:40
-	47	plasma near5 (CVD or chemical near2 vapor near2 deposit$5 or ale or ald or atomic near2 layer near2 (deposit$5 or epitax$4)).ti. and bias$5 near10 (susceptor or holder)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 16:56
-	418	rotary near2 ball near2 valve	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:00
-	1	rotary near2 ball near2 valve and vapor near2 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:00
-	8	rotary near2 ball near2 valve near5 (gas$4 or vapor$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:02
-	17	rotary near5 valve same ball same deposit$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:03
-	141	rotary near5 valve same ball same (gas$4 or vapor$5 or vapour$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:05

–	7	rotary near5 valve same ball and vapor near2 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:06
–	5	rotary near5 valve near5 ball and vapor near2 deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:06
–	84	rotary near5 valve near5 ball and deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:06
–	71	rotary near5 valve near5 ball same (gas$5 or reactant$5 or precursor$5 or vapor$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/12 17:07
–	201	gas$5 near2 curtain near10 (separat$5 or isolat$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 15:56
–	107	gas$5 near2 curtain near10 (separat$5 or isolat$6) same chamber	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:24
–	24	inert near5 gas$5 near2 curtain near10 (separat$5 or isolat$6) same chamber	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:26
–	949406	inert near5 gas$5 near2 curtain and cluster enar5 tool	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:27
–	1	inert near5 gas$5 near2 curtain and cluster near5 tool	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:27
–	0	inert near5 gas$5 near2 curtain same cluster	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:27
–	26	inert near5 gas$5 near2 curtain and cluster	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/13 16:28
–	75	inert near5 gas$5 near2 curtain same deposit$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:47
–	3396	(wafer or substrate) near10 bias$5 and plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:56
–	626	(wafer or substrate) near10 bias$5 same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:56

-	513	(wafer or substrate) near5 bias$5 same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:56
-	341	(wafer or substrate) near2 bias$5 same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:02
-	0	(wafer or substrate) near2 bias$5 same plasma near2 (CVD or vapor near2 deposit$5) and plamsa.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:02
-	93	(wafer or substrate) near2 bias$5 same plasma near2 (CVD or vapor near2 deposit$5) and plasma.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:15
-	1	(wafer or substrate) near2 bias$5 near10 advantag$5 same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; DERWENT; IBM_TDB	2004/08/16 11:15
-	33653	(wafer or substrate) near2 bias$5 near10 improv$6same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; DERWENT; IBM_TDB	2004/08/16 11:16
-	9	(wafer or substrate) near2 bias$5 near10 improv$6 same plasma near2 (CVD or vapor near2 deposit$5)	USPAT; US-PGPUB; EPO; DERWENT; IBM_TDB	2004/08/16 11:30
-	1	5879459.pn. and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:16
-	0	plasma near5 clean$5 same substrate near5 bais$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:34
-	139	plasma near5 clean$5 same substrate near5 bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:37
-	0	plasma near5 clean$5 same substrate near5 bias$5 and (ald or ale or atomic near2 layer near2 (epitax$5 or deposit$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 11:37
-	387	plasma near2 etch$5 same substrate near2 bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:17
-	75	plasma near2 etch$5 near5 substrate near2 bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:18
-	12	plasma near2 clean$5 near5 substrate near2 bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:18

-	60	substrate near2 bias$5 near10 plasma and showerhead near10 plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:51
-	450	cluster near5 tool same plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:51
-	131	cluster near5 tool same plasma and plasma near10 bias$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:51
-	64	cluster near5 tool same plasma and plasma near10 bias$5 near10 (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:54
-	149	cluster same plasma and plasma near10 bias$5 near10 (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 13:57
-	38	(US-4545136-$ or US-6040021-$ or US-5125360-$ or US-4763602-$ or US-6444277-$ or US-6635965-$ or US-6541353-$ or US-6143082-$ or US-6387185-$ or US-5997588-$ or US-5351706-$ or US-5102098-$ or US-5656338-$ or US-6042652-$ or US-6174377-$ or US-5879459-$ or US-6136725-$ or US-6296711-$ or US-5866213-$ or US-5251148-$ or US-6056824-$).did. or (US-20030141820-$ or US-20040038529-$ or US-20040065258-$ or US-20030232506-$ or US-20020170671-$ or US-20030109094-$ or US-20020108714-$ or US-20040005753-$ or US-20020100418-$ or US-20020195056-$ or US-20010013313-$ or US-20010011526-$ or US-20010016364-$ or US-20040023516-$ or US-20030198587-$ or US-20010007244-$ or US-20020046705-$).did.	USPAT; US-PGPUB	2004/08/16 13:55
-	15	((US-4545136-$ or US-6040021-$ or US-5125360-$ or US-4763602-$ or US-6444277-$ or US-6635965-$ or US-6541353-$ or US-6143082-$ or US-6387185-$ or US-5997588-$ or US-5351706-$ or US-5102098-$ or US-5656338-$ or US-6042652-$ or US-6174377-$ or US-5879459-$ or US-6136725-$ or US-6296711-$ or US-5866213-$ or US-5251148-$ or US-6056824-$).did. or (US-20030141820-$ or US-20040038529-$ or US-20040065258-$ or US-20030232506-$ or US-20020170671-$ or US-20030109094-$ or US-20020108714-$ or US-20040005753-$ or US-20020100418-$ or US-20020195056-$ or US-20010013313-$ or US-20010011526-$ or US-20010016364-$ or US-20040023516-$ or US-20030198587-$ or US-20010007244-$ or US-20020046705-$).did.) and cluster	USPAT; US-PGPUB	2004/08/16 13:55

–	14	((US-4545136-$ or US-6040021-$ or US-5125360-$ or US-4763602-$ or US-6444277-$ or US-6635965-$ or US-6541353-$ or US-6143082-$ or US-6387185-$ or US-5997588-$ or US-5351706-$ or US-5102098-$ or US-5656338-$ or US-6042652-$ or US-6174377-$ or US-5879459-$ or US-6136725-$ or US-6296711-$ or US-5866213-$ or US-5251148-$ or US-6056824-$).did. or (US-20030141820-$ or US-20040038529-$ or US-20040065258-$ or US-20030232506-$ or US-20020170671-$ or US-20030109094-$ or US-20020108714-$ or US-20040005753-$ or US-20020100418-$ or US-20020195056-$ or US-20010013313-$ or US-20010011526-$ or US-20010016364-$ or US-20040023516-$ or US-20030198587-$ or US-20010007244-$ or US-20020046705-$).did.) and cluster and plasma	USPAT; US-PGPUB	2004/08/16 13:55
–	3	((US-4545136-$ or US-6040021-$ or US-5125360-$ or US-4763602-$ or US-6444277-$ or US-6635965-$ or US-6541353-$ or US-6143082-$ or US-6387185-$ or US-5997588-$ or US-5351706-$ or US-5102098-$ or US-5656338-$ or US-6042652-$ or US-6174377-$ or US-5879459-$ or US-6136725-$ or US-6296711-$ or US-5866213-$ or US-5251148-$ or US-6056824-$).did. or (US-20030141820-$ or US-20040038529-$ or US-20040065258-$ or US-20030232506-$ or US-20020170671-$ or US-20030109094-$ or US-20020108714-$ or US-20040005753-$ or US-20020100418-$ or US-20020195056-$ or US-20010013313-$ or US-20010011526-$ or US-20010016364-$ or US-20040023516-$ or US-20030198587-$ or US-20010007244-$ or US-20020046705-$).did.) and cluster same plasma	USPAT; US-PGPUB	2004/08/16 13:55
–	138	cluster near5 tool and plasma near10 bias$5 near10 (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:33
–	368	gas$5 near5 distribut$5 near10 reactors!	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:34
–	107	gas$5 near5 distribut$5 near10 reactor near5 plurality	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:35
–	64	gas$5 near5 distribut$5 near10 reactor near plurality	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:55
–	19	showerhead near10 (triangular or delta or linear)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:57
–	1	showerhead near10 (triangular or delta)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 16:58

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| - | 175 | showerhead near10 shap$5 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/16 16:58 |
| - | 56 | showerhead near10 shap$5 near10 (gas$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/08/16 16:58 |